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(54) Title: TOP COAT COMPOSITION, AND METHOD FOR PRODUCING RESIST PATTERN AND METHOD FOR PRO-
DUCING DEVICE USING SAME

(57) Abstract: To provide a top coat composition suitable for immersion lithography. A top coat composition comprising a graft polymer (A) and a solvent (B), the graft polymer (A) comprising a skeleton polymer (AB) moiety and a side chain polymer (AG) moiety; and the side chain polymer (AG) having a cLogP of 15 to 100, and the skeleton polymer (AB) having a cLogP of 1.10 to 3.00. The top coat composition is a high-performance material that can be used in the nanotechnology process of semiconductor device manufacturing, for example, in the manufacturing process of semiconductor devices that control liquid crystal, quantum dot, or OLED displays formed on a substrate.



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